

OS20 Advanced surface processing

OS20-01 Formation of Heterostructured Si Thick Films in Atmospheric Pressure Very High-Frequency Plasma
Afif Hamzens, Shota Mochizuki, Hiromasa Ohmi and Hiroaki Kakiuchi
Osaka University

OS20-02 Study on mechanism of surface instability in Sn-Bi alloy lapping plate
Bei Hu, Wenjun Zhou and Kensuke Tsuchiya
Univerisity of Tokyo

OS20-03 Porous Silicon Oxide Formation Using Atmospheric-Pressure Very High-Frequency Plasma for Single-Layer Anti-Reflection Coatings on Transparent Substrates
Leapheng Uon, Naoto Mizusawa, Reo Yamauchi, Hiromasa Ohmi and Hiroaki Kakiuchi
Osaka University

OS20-04 Surface modification of Si-MEMS using electron beam induced silicon nanodots
Abhiraj Singh, Shingo Kammachi, Nobutaka Goami, Muncyuki Naito, Ryosuke Matsumoto and Takahiro Namazu

OS20-05 Ultrasonic-assisted fabrication of water-dispersed photonic crystals for self-reporting surface pressure sensor application
Daniel Saldivar-Ayala and Takahiro Namazu
Kyoto University of Advanced Science

OS20-07 Effect of substrate temperature on mechanical property of amorphous silicon carbon nitride films deposited by surface-wave plasma CVD
Ippei Tanaka, Yuki Hattori, Yuki Hatae and Yasunori Harada

OS20-08 Effect of Containing Copper Particles on Mechanical Characteristics of Sintered Ag film for SiC Die Bonding
Chessadakorn Chantawong, Michiko Shindo, Mitsuhiro Nishida and Takahiro Namazu
Kyoto University of Advanced Science

OS20-09 Evaluation of adhesion resistance of PVD films to hot dip galvanized and pure Zn
Yusuke Ushiro, Ippei Tanaka, Yasunori Harada, Yuji Nanba and Takashi Ogisu
Umetoku Co., Ltd.

<p>OS20-10 W-Ti alloy films prepared by dual source dc magnetron sputtering Hibiki Okada and Shozo Inoue University of Hyogo</p>
<p>OS20-11 The effect of ion irradiation on the growth of sputtered metal thin films Tatsuhiro Inoue, Shinpei Nagai and Shozo Inoue University of Hyogo</p>
<p>OS20-12 The effect of concentration modulation on friction properties of diamond films synthesized by microwave plasma CVD Ryota Ohnishi, Ippei Tanaka, Natsuki Kawaguchi and Yasunori Harada University of Hyogo</p>
<p>OS20-13 Improvement of etching rate of gallium nitride substrates by atmospheric pressure plasma with H₂/O₂/He gas Motoki Nabata, Genta Nakaue, Daisetsu Toh, Jumpei Yamada, Kazuto Yamauchi and Yasuhisa Sano Osaka University</p>
<p>OS20-14 Damage-free Processing of Extremely Narrow Spaces via High-precision Etching Using High-pressure Plasma That Exceeds Atmospheric Pressure Masafumi Miyake, Shotaro Matsumura, Iori Ogasahara, Taito Osaka, Jumpei Yamada, Daisetsu Toh, Kazuto Yamauchi, Makina Yabashi and Yasuhisa Sano Osaka University</p>
<p>OS20-15 Mechanical Reliability of Sintered Ag Die Attach Assemblies with Al/Ni Rapid Heat Treatment Hiroya Saegusa, Daisuke Yasugi and Takahiro Namazu Kyoto University of Advanced Science</p>
<p>OS20-18 Strength prediction of metal-polymer joints using machine learning from metal surface images Zhongqi Cui, Shuohan Wang, Yuuka Ito, eiji Yamaguchi, Fuminobu Kimura and Yusuke Kajihara The university of Tokyo</p>
<p>OS20-19 Enhancing Wear Resistance of IN 625 Alloy Through Parameter Optimization in Wire Arc Additive Manufacturing Ankit Kumar, Mayank Arun Sontakke, Gurminder Singh and Rahul S. Mulik The Indian Institute of Technology Bombay, INDIA</p>

OS20-20 Polishing of Hardened Steel Components
using Magnetic Abrasive Finishing

Hiroyuki Matsumura, Julian Long and Hitomi Yamaguchi
University of Florida

OS20-22 Surface texture creation mechanisms and
surface properties of intermittent burnishing process

Masato Okada, Hayato Nakagawa, Makoto Nikawa and
Shunki Kitagawa
University of Fukui